

### **High-Purity Chemicals in Electronic Applications**

Training guide for filtration products



aerospace climate control electromechanical filtration fluid & gas handling hydraulics pneumatics process control sealing & shielding



ENGINEERING YOUR SUCCESS.

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For technical or application support related to our fluid filtration solutions, please call our toll free number **877 784 2234** or email **dhpsales.na@parker.com** 

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Parker domnick hunter has a continuous policy of product development and although the Company reserves the right to change specification, it attempts to keep customers informed of any alterations. This publication is for general information only and customers are requested to contact our Process Filtration Sales Department for detailed information and advice on a product's suitability for specific applications. All products are sold subject to the company's Standard conditions of sale.

Schematic

Introduction

Selection Process

Applications

Ultra-Pure Water (UPW)

High-Purity Solvents Isopropyl Alcohol (IPA)

High-Purity Acids & Bases Hydrofluoric Acid

High-Purity Acids & Bases Sulfuric Acid

High-Purity Acids & Bases Hydrogen Peroxide

Services

Selection Matrix

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## Introduction

# Providing a cost-effective filtration technology that ensures consistent quality and process optimization

High-purity chemicals and materials are essential in manufacturing microelectronics devices that are enabling advances in work, life science, communications, transportation, efficient lighting, entertainment, shopping, and many other areas that affect our lives.

Parker domnick hunter's proven product range and applications experience in the manufacturing of these high-purity chemicals, chemistries, and solvents allows our customers to meet the highpurity requirements that enable constant technical advancement of their customers. While each application is unique, we can often divide high-purity applications into the following broad processes:

- Ultra-pure water is needed to enable production of liquid high-purity chemical, or to dilute concentrated chemical into the concentration required by the customer.
- Specialty chemical-vapor filtration which is unique to polysilicon production.
- Distillation in some processes may be done in a very aggressive, high-temperature environment requiring a special filtration solution.
- Venting of tanks with hydrophobic filters to relieve gas pressure build-up.
- Anhydrous and other industrial liquid raw materials may require filtration from tankers, pipelines, or other large vessels before they are introduced to the high-purity manufacturing system.
- Pre-filtration or clarification through the manufacturing process is typical and necessary to guarantee quality specifications throughout the process.
- Final package filtration is the last particle barrier and the final critical filtration step in the high-purity manufacturing process.

Given the variations of these processes for high-purity chemicals, chemistries, and solvents, it is critical to consider the operating parameters when selecting filtration for each stage of manufacturing.

As our customers require fewer and smaller particles and the need for lower metal extractables increases, it is essential for us to fully understand their applications and process demands. In addition to helping our customers achieve their final specification, we must recommend filtration solutions that minimize process downtime and reduce product waste. The total cost of ownership must be considered without compromising the quality of the end product.

#### **Market Applications**

- High-purity concentrated acids
- High-purity acid blends
- High-purity bases
- High-purity alkaline solutions
- High-purity solvents
- Some photoresists and polyimides
- Anti-reflective coatings
- Developers negative and positive
- Organic solvents used to strip photoresist polymer
- CMP base chemicals acids or bases
- High-purity plating solutions
- Trichlorosilane vapor and liquid



Introduction

**Schematic** 

High-Purity Acids & Bases Hydrofluoric Acid

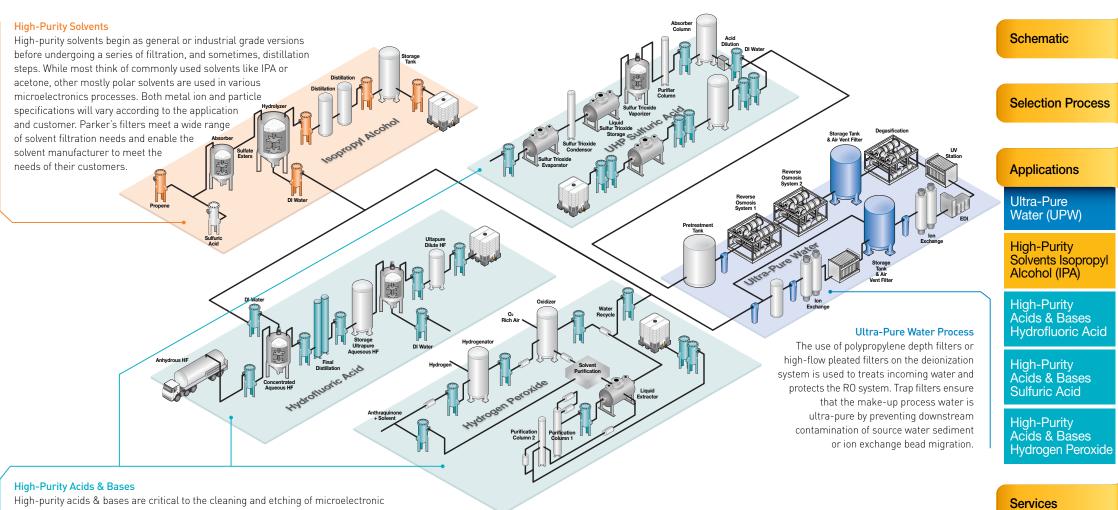
High-Purity Acids & Bases Sulfuric Acid

High-Purity Acids & Bases Hydrogen Peroxide

Services

Selection Matrix

## **High-Purity Chemical Application Overview**



High-purity acids & bases are critical to the cleaning and etching of microelectronic devices, especially semiconductors. Parker dh's lineup of filters are well suited for achieving the challenging particle and ionic specifications the chemical companies need to meet. Filtration is progressive, getting tighter throughout the process. Materials of construction must not only be highly compatible and provide good performance, but must also offer outstanding value. While polypropylene may be compatible in a particular acid or base for one manufacturer, it may not be suitable for another whose end user customers require ultra low metal extractables. Parker can meet the needs of both customers.

For detailed products in each process application, see pages 5 - 9.

Selection Matrix

Introduction

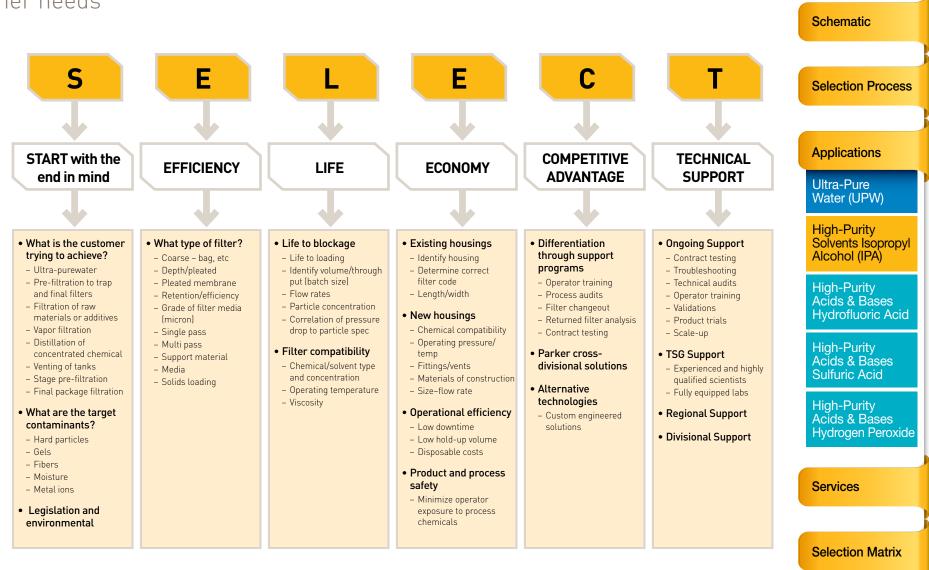
## **Selection Process**

### Identifying customer needs

In order to meet filtration specifications, physical and chemical conditions of the process have to be considered.

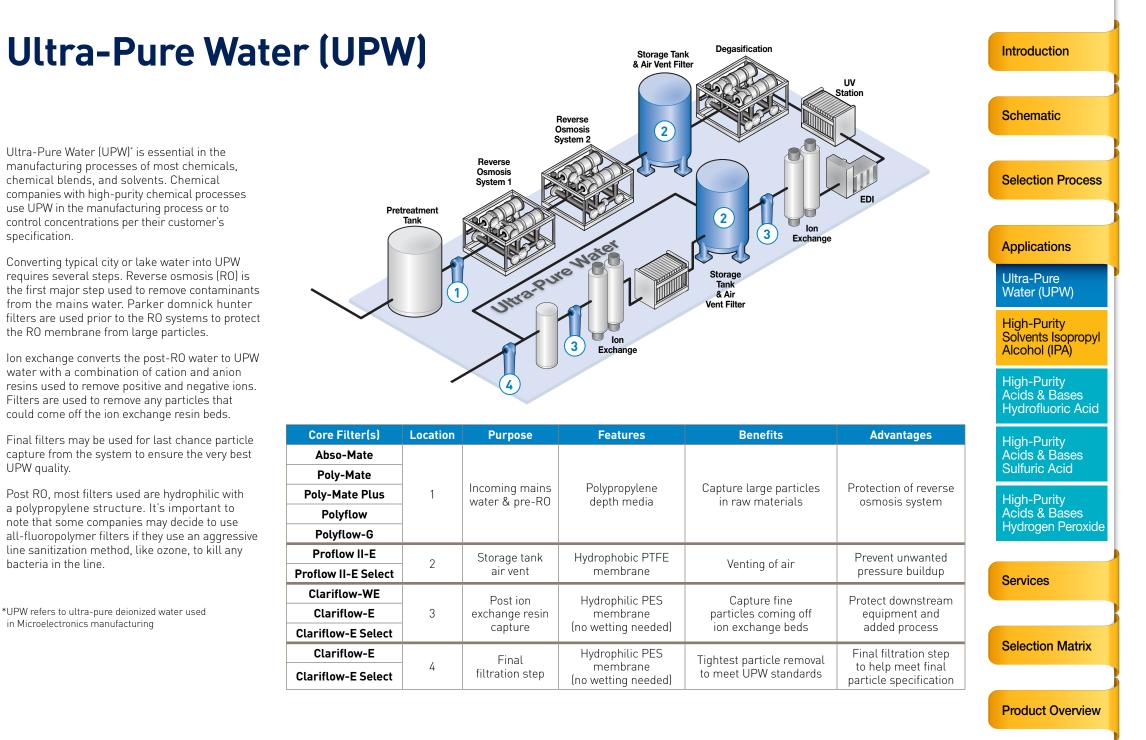
It is therefore essential that a methodical process for identifying the customer's needs is followed.

The SELECT process builds on principles used to select the optimized filtration solution for the high-purity chemical manufacturer.



**Product Overview** 

Introduction



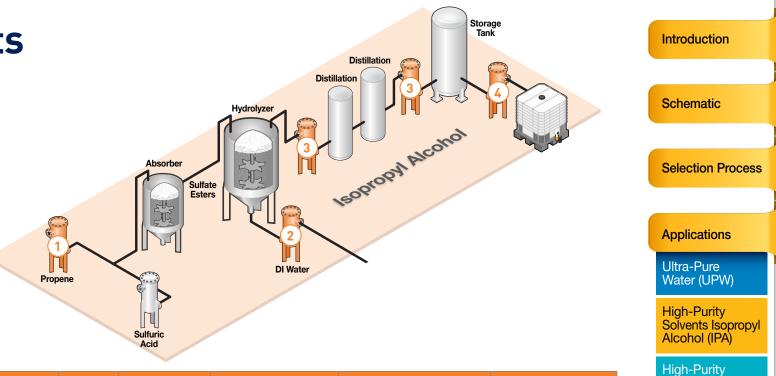
### **High-Purity Solvents** Isopropyl Alcohol (IPA)

Isopropyl Alcohol (IPA) is the most common solvent used in semiconductor manufacturing. It may be used to rinse wafers in certain processes where water contact is not desirable. IPA is also used to dry wafers and other Microelectronics devices since it will not streak or leave watermarks. While there are different methods of manufacturing IPA, a common one is through the combination of propene and sulfuric acid to create sulfate esters. Parker melt blown and pleated depth filters may be used to filter these raw materials.

The hydrolization process combines the sulfate esters and Ultra-Pure Water (UPW). A hydrophilic filter may be used to filter incoming UPW. As the newly created IPA leaves the hydrolyzer, it may pass through filtration prior to other process steps including distillation.

The number of distillation steps will depend on the level of purity required. Though not shown here, some manufacturers may use filters during or between distillation steps. Following distillation, a series of filtration steps may be used to further reduce inline particle size and quantity.

Final package filtration is a last chance particle removal step. This is typically where inline particle counters will be used to monitor particle size and quantity. Here, filters will be tighter than upstream filters in the manufacturing process. Micron rating will depend on the end user particle specification.



Core Filter(s)	Location	Purpose	Features	Benefits	Advantages	Acids & Bases		
Abso-Mate	1		Polypropylene depth media	Capture large particles in raw materials	Protection of absorption process	Hydrofluoric Acid		
Poly-Mate		Incoming raw materials				High-Purity		
Poly-Mate Plus						Acids & Bases		
Polyflow		materials				Sulfuric Acid		
Polyflow-G					High-Purity			
Clariflow-WE					Provide consistent	Acids & Bases		
Clariflow-E	2	DI water	Hydrophilic PES membrane	Removal of particles in UPW down to 0.02 microns	source of UPW to hydrolyzer	Hydrogen Peroxide		
Clariflow-E Select								
Chemflow-PE						Services		
Chemflow-PE Select	3	Pre and post	PTFE membrane on	Eine nentiele neueronal	Protect and enhance	UCIVICES		
Proflow II-E	- 3	3	distillation	either HDPE or PP support structure		distillation process	distillation process	
Proflow II-E Select								
Chemflow-PE					Final filtration atom	Selection Matrix		
Chemflow-PE Select		4 Final package	PTFE membrane on either HDPE or PP support structure	Fine particle removal	Final filtration step to help meet final product particle specification			
Proflow II-E								
Proflow II-E Select						Product Overview		

### **High-Purity Acids & Bases** Hydrofluoric Acid

High-purity hydrofluoric (HF) acid begins with the mixing and chemical interaction of sulfuric acid and dry fluorspar (CF2). The result of mixing those in a rotary kiln is HF gas. The HF gas is condensed then distilled to form anhydrous hydrofluoric acid.

In this diagram, the industrial anhydrous HF is delivered via tanker or pipeline to become ultra-pure HF commonly used in semiconductor wafer etch and clean processes. Parker domnick hunter membrane filters with either HDPE or PFA structures may be used throughout the manufacturing process.

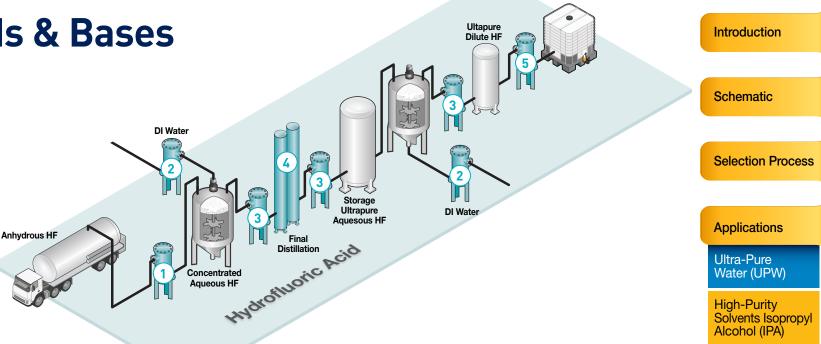
Distillation is an important step in producing ultra-pure hydrofluoric acid. The aggressive nature of the acid combined with temperatures high enough to vaporize the HF make this a challenging filter application. For that reason, only 100% fluoropolymer filters can be used.

The HF vapor can pass through the PTFE membrane, then re-condense in to a purer form with ultra low contaminants. As the ultra-pure concentrated HF exits the distillation process, a filtration step to remove additional particles may be present.

From here, the ultra-pure concentrated HF may be blended with ultra-pure water to various desired concentrations.

Parker domnick hunter filters ensure process consistency and enable the HF manufacturer to meet the final particle specification for their end user customers.

It's important to note that while polypropylene filters, like Parker's Proflow-II-E, could be used in dilute HF, both HDPE and PFA are considered to be more chemically robust and would typically be recommended.



Core Filter(s)	Location	Purpose	Features	Benefits	Advantages	High-Purity	
Chemflow-PE		Optional Incoming raw materials	PTFE membrane on either HDPE or PFA support structure	More open ratings to capture large particles in raw materials	Process particle control	Acids & Bases Hydrofluoric Acid	
Chemflow-PE Select							
Fluoroflow						High-Purity	
Fluoroflow-HSA						Acids & Bases Sulfuric Acid	
Clariflow-WE					Provide consistent		
Clariflow-E	2	DI water	Hydrophilic PES membrane	Removal of particles in UPW down to 0.02 microns	source of DIW to	High-Purity	
Clariflow-E Select					hydrolyzer	Acids & Bases Hydrogen Peroxide	
Chemflow-PE				Fire contints are seen	Process particle		
Chemflow-PE Select	3	Stage/					
Fluoroflow	3	3	pre-filtration/ blending	either HDPE or PFA support structure	Fine particle removal	control	Services
Fluoroflow-HSA							
Fluoroflow	4	High temp acid	100% fluoropolymer	Temperature rating	Coalesce water and		
Fluoroflow-HSA		distillation	construction	up to 180C	particle removal	Selection Matrix	
Chemflow-PE	- 5	5 Fine particle removal	PTFE membrane on either HDPE or PP support	Fine particle removal	Final filtration step to help meet final	Colocation maanx	
Chemflow-PE Select							
Fluoroflow						Dreduct Outering	
Fluoroflow-HSA							Product Overview

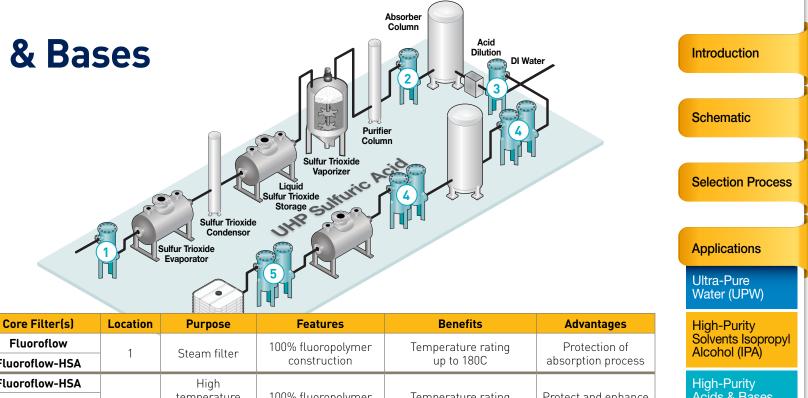
### High-Purity Acids & Bases Sulfuric Acid

Sulfuric acid is highly used with either hydrogen peroxide or ozonated UPW to create an intended exothermic reaction. The added energy to this aggressive acid is ideal for removing hard-baked photoresists and most organic contaminants from the surface of silicon production wafers.

A common method of creating sulfuric acid begins by mixing oleum and steam to produce sulfur trioxide vapor. Filters may be used to remove large particles and provide protection to the evaporator.

The SO3 is condensed then vaporized again just before entering a series of purifier columns. The number of purifiers will depend on the H2SO4 specification. Exiting the absorber column is pure concentrated sulfuric acid.

The pure concentrated acid is cooled and carefully diluted into usable concentrations. From there, the acid goes through a series of membrane filtration steps, each succeeding step tighter than the previous until particle specifications are met and the product is packaged for the end user.



Fluoroflow-HSA	I	Steam filler	construction	up to 180C	absorption process	
Fluoroflow-HSA	2	2 2 High temperature acid vaporization	100% fluoropolymer construction	Temperature rating up to 180C	Protect and enhance distillation process	High-Purity
Fluoroflow-Select						Acids & Bases Hydrofluoric Acid
Fluoroflow-XL						
Clariflow-WE						High-Purity
Clariflow-E	3	DI water	Hydrophilic PES membrane	Removal of particles in UPW down to 0.02 microns	Provide consistent source of UPW	Acids & Bases Sulfuric Acid
Clariflow-E Select			membrane			
Chemflow-PE			PTFE membrane on either HDPE,PFA or PP support structure	Fine particle removal	Process particle control	High-Purity
Chemflow-PE Select		4 pre-filtration/ either HDPE,PFA or Fine particle removal				Acids & Bases Hydrogen Peroxide
Proflow II-E	1					
Proflow II-E Select	4					
Fluoroflow-HSA						Services
Fluoroflow-Select						
Chemflow-PE	- 5 Final package					
Chemflow-PE Select				Fine particle removal	Final filtration step to help meet final product particle specification	Selection Matrix
Proflow II-E		Final nackada	PTFE membrane on			
Proflow II-E Select			either HDPE, PFA or PP support structure			
Fluoroflow-HSA						Dreduct Origini
Fluoroflow-Select						Product Overview

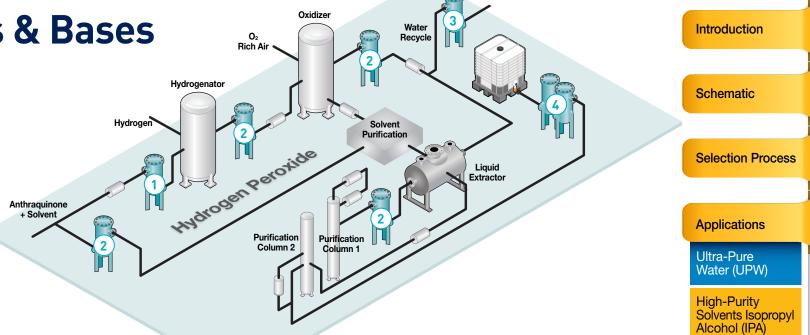
### **High-Purity Acids & Bases** Hydrogen Peroxide

Hydrogen peroxide is made in a series of steps. A hydrocarbon-based "work-solution" is fed to the hydrogenator along with a stream of hydrogen where hydrogenation occurs over a bed of Ni or Pd catalysts.

The first filtration step is used to capture catalyst particles from the hydrogenated fluid.

In the oxidizer, oxygen-rich air is introduced to the work solution to reverse the previous reaction. The resulting work-solution contains about 40%  $H_2O_2$  by weight as it goes into the liquid extractor. Water is fed into the extractor and since the  $H_2O_2$  is miscible in water while the solvent is not, the water-peroxide layer can be removed and sent to the purification columns.

In the purification columns, the water-peroxide mixture is further concentrated and purified. For UHP hydrogen peroxide, multiple columns may be used.



Core Filter(s)	Location	Purpose	Features	Benefits	Advantages	High-Purity
Abso-Mate	_	Incoming raw materials	Polypropylene depth media	Capture large particles in raw materials	Protection of evaporator	Acids & Bases
Poly-Mate						Hydrofluoric Acid
Poly-Mate Plus	1					High-Purity
Polyflow						Acids & Bases
Polyflow-G						Sulfuric Acid
Chemflow-PE		Stage/ pre-filtration/ blending	PTFE membrane on either HDPE or PP support structure	Fine particle removal	Process particle control	High-Purity
Chemflow-PE Select	2					Acids & Bases Hydrogen Peroxide
Proflow II-E	2					riyulogen Feloxide
Proflow II-E Select						
Clariflow-WE		DI water	Hydrophilic PES membrane	Removal of particles in UPW down to 0.02 microns	Provide consistent source of UPW to liquid reactor	Services
Clariflow-E	3					
Clariflow-E Select						
Chemflow-PE	4		PTFE membrane on either HDPE, PP or PFA support structure	Fine particle removal	Final filtration step to help meet product specifications	Selection Matrix
Chemflow-PE Select		Final Package				Selection Matrix
Proflow II-E						
Proflow II-E Select						
Fluoroflow						Product Overview

### **Services** Technical Support Group (TSG)

In these industries, manufacturers and end-users face stringent environmental and operational compliances, where the trend is to ensure low Volatile Organic Compounds (VOC) exposure and spillage of hazardous waste while providing a more user friendly process environment. Combined with the market demands for high quality products, this means that the raw materials and chemistries used in formulations result in higher manufacturing costs.

Parker domnick hunter is committed to providing comprehensive technical support of our products through our global sales network and dedicated technical support group. Our team of trained scientists, engineers and technicians is available to answer questions on the capabilities of our products, assist customers to select, specify and design filtration systems to meet specific user requirements, and provide a range of advisory and troubleshooting services.

We provide technical support to assist in training operators on a wide range of activities related to using our products, system sizing and performance optimization.

Results can be utilized to manipulate pre and final filter trains to achieve the desired throughput and quality without over processing.

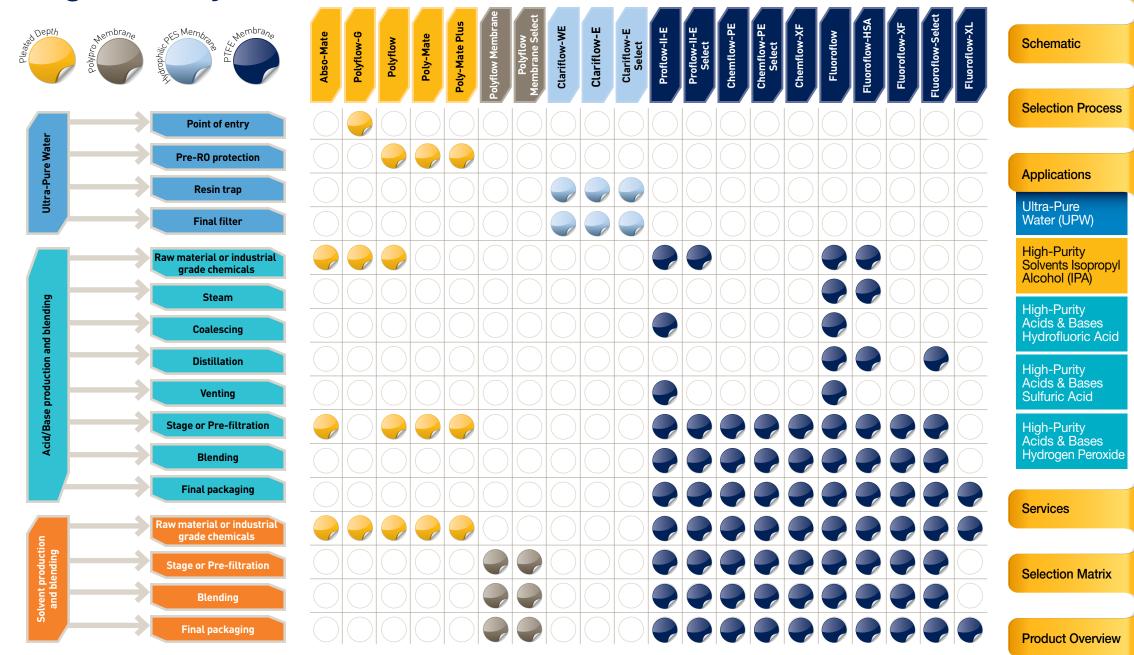
#### Services Overview



#### Introduction

**Schematic** 

### **High-Purity Chemicals Selection Matrix**



Introduction

#### **PTFE Membrane Filter Cartridges**

#### Chemflow<sup>®</sup>-PF

- Good flow rates
- Good lifetime
- Wet-pack option for quick installation PTFE/HDPE construction for chemical resistance
- 100% integrity tested in cleanroom environment

Chemflow-PE provides a low metals, economical alternative to all-fluoropolymer cartridges. Ideally suited for final packaging of high-purity chemicals and solvents and most lower temperature chemical delivery and wet process (<60°C) applications.





Chemflow<sup>®</sup>-PF Select

- PTFE/HDPE construction for chemical resistance
- 100% integrity tested in cleanroom environment

The addition of the SELECT pleat technology provides a high-flow, low metals, and economical alternative to all-fluoropolymer high surface area cartridges. Ideally suited for final packaging of high-purity chemicals and solvents and many low temperature chemical delivery and wet process (<60°C) applications.



#### Chemflow<sup>®</sup>-XF

- Highest flow rates in the industry for a 2.75" wide cartridge Long lifetime
- Wet-pack option for quick installation
- PTFE/HDPE construction for chemical resistance
- 100% integrity tested in cleanroom environment

The asymmetric PTFE membrane provides unmatched flow rates and on-stream life to help improve throughput and reduce filtration costs. Ideally suited for final packaging of high-purity chemicals and solvents and many low temperature chemical delivery and wet process (<60°C) applications.

#### Fluoroflow®

- · Economical all-fluoropolymer cartridge
- High particle retention
- Wet-pack option for guick installation
- All-fluoropolymer for maximum chemical resistance
- 100% integrity tested in cleanroom environment

Fluoroflow is an economical all-fluoropolymer solution for low to medium flow high purity chemical applications that require the highest chemical resistance. This filter is ideally suited for nearly all high-purity chemical and solvent manufacturing applications including those requiring a high temperature rating (150°C).

#### Fluoroflow<sup>®</sup>-XF

- Highest flow rates in the industry for a 2.75" wide cartridge
- High flux asymmetric PTFE membrane rates for increased flow
- Wet-pack option for quick installation
- All-fluoropolymer for maximum chemical resistance
- 100% integrity tested in cleanroom environment

This cartridge provides excellent flow and chemical resistance for the most aggressive applications up to 150 °C. Fluoroflow-XF is ideally suited for high-purity chemical manufacturing processes and recirculated clean, etch, or plating applications where particle removal efficiency is improved with high bath turnover.

#### Proflow<sup>™</sup> II-F

- · Economical, high-purity chemical and solvent filtration
- Good liquid and gas flow rates
- Wet-pack option for quick installation
- PTFE/ PP construction for high chemical resistance
- 100% integrity tested in cleanroom environment

Proflow-II-E uses a PTFE membrane with high purity polypropylene supports to provide an economical yet high-purity filtration solution for high-purity chemical, solvent and gas applications. This filter is ideal for many high-purity chemical and solvent manufacturing applications.

#### Fluoroflow<sup>®</sup>-HSA

Increased filtration area for longer life

- High particle retention
- Wet-pack option for guick installation
- All-fluoropolymer for most maximum chemical resistance
- 100% integrity tested in cleanroom environment

This cartridge is a high surface area all-fluoropolymer solution for medium flow high purity chemical applications that require the highest chemical resistance and desire longer life. This filter is ideally suited for nearly all high-purity chemical and solvent manufacturing applications including those requiring a high temperature rating (150°C).

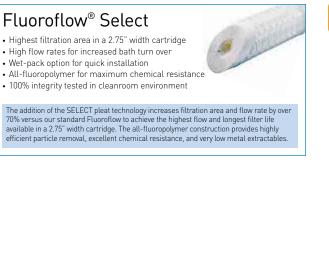
#### Fluoroflow<sup>®</sup>-XI

- Extra-high filtration area in a 3.25" wide cartridge
- Highest flow rates for maximum bath turn over
- Wet-pack option for guick installation
- Ultraclean option for absolute cleanliness
- 100% integrity tested in cleanroom environment

Uses a larger diameter cartridge (3.25") combined with our unique SELECT pleating technology to achieve our highest surface area, highest-flow all-fluoropolymer filter. Fluoroflow-XL is ideal for high-loading, aggressive, high-purity processes where performance is dependent on high flow, efficient particle removal, and ultra-low metal extractables.

#### Proflow<sup>™</sup> II-F Select

- Economical, high-purity chemical and solvent filtration
- High surface-area SELECT pleating for excellent liquid flow rates
- Wet-pack option for quick installation
- PTFE/ PP construction for chemical resistance
- 100% integrity tested in cleanroom environment
- An economical, yet high-performance filter cartridge for high-purity chemical and solvent applications, the Proflow II-E Select uses a PTFE membrane along with polypropylene supports. With SELECT pleating, liquid flow rates are increased by up to 50% verses our standard Proflow II-E.





**Applications** 

Ultra-Pure

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Acids & Bases Hydrofluoric Acid

High-Purity Acids & Bases Sulfuric Acid

High-Purity Acids & Bases Hydrogen Peroxide

Services

Selection Matrix







#### **Pleated Depth Filter Cartridges**

#### Abso-Mate®

- · Non-fiber releasing and low extractables
- Single-piece construction eliminates bypass concerns
- All-polypropylene construction offers wide chemical compatibility with most chemicals
- Absolute rated for consistent and reliable performance [99,98%]

Cost-effective and absolute rated for capturing particles 0.2 to 70 µm in size. This pleated melt blown cartridge is of all-polypropylene construction, and without adhesives that could potentially contaminate fluids.

#### Fulflo<sup>®</sup> Poly-Mate<sup>™</sup>

- All Polypropylene construction maximizes chemical resistance
- Pleated surface area offers extended service life. low pressure drop and high flow capacity
- One-piece, continuous to 40 inches length, integrally sealed pleated filter media
- Non-fiber releasing polypropylene construction

A unique combination of polypropylene melt blown and spun-bonded pleated media provides retention ratings of 0.5 to 60 µm at 99% efficiency.

#### **Polypropylene Membrane Filter Cartridges**

#### Polyflow<sup>®</sup> Membrane

- Highly-retentive polypropylene membrane
- Wide range of configurations and ratings
- Wet-pack option for guick installation
- 100% thermally welded virgin polypropylene construction
- 100% integrity tested in cleanroom environment

This all-polypropylene filter cartridge is optimized for use in certain electronics applications such as the manufacturing of high-purity solvents and most G or I-line photoresists. Every cartridge is fabricated in a clean room environment, pre-flushed with 18 megohm-cm ultrapure DI water, and 100% integrity tested.

#### Hydrophilic PES Membrane Filter Cartridges

#### Clariflow<sup>®</sup>-F

- High-retention hydrophilic PES membrane
- Good flow rate DI water and dilute acids and bases.
- Rating down to 0.02 microns
- 100% integrity tested in cleanroom environment

Clariflow-E filter cartridges are optimized for semiconductor DI water and dilute aqueous-based chemicals. A mirrored-anisotropic hydrophilic PES (Polyethersulfone) membrane allows for quick and convenient startup without the need for pre-wetting.

#### Polyflow®

- High-retention depth matrix for economical prefiltration
- High flow rate and long service life reduce processing time
- Wide variety of configurations and ratings
- Broad chemical compatibility allows use in most applications
- Thermally bonded virgin polypropylene construction minimizes extractables

Thermally bonded, absolute rated 100% virgin polypropylene to provide absolute filtration cartridge features a random-fiber polypropylene depth matrix to provide excellent retention efficiencies. Ideally suited for most high-purity chemical and solvent pre-filtration applications.

### Fulflo® Poly-Mate<sup>™</sup> Plus

- Fixed pore construction provides
- ultimate particle retention
- Offers high flow rates and extended service life
- Non-fiber releasing enabling consistent quality filtration performance
- One piece integral construction for maximum cartridge integrity

A unique combination of polypropylene melt blown and spun-bonded pleated media provides high surface area at retention ratings of 0.25 to 100 µm at 90% efficiency.

#### Polyflow<sup>®</sup> Membrane Select

- Highly-retentive polypropylene membrane
- Unique SELECT pleating technology for higher flow and longer life
- · Wet-pack option for guick installation
- 100% thermally welded virgin polypropylene construction
- 100% integrity tested in cleanroom environment

Polyflow-Membrane-Select is a higher surface area, all-polypropylene filter cartridge ideal for use in certain electronics applications such as the manufacturing of high-purity solvents and most G or I-line photo resists. Every cartridge is fabricated in a clean room environment. pre-flushed with 18 megohm-cm ultrapure DI water, and 100% integrity tested.



#### Polyflow<sup>®</sup>-G

- Depth matrix for economical prefiltration
- High flow rate and long service life reduce processing time
- Wide variety of configurations and ratings
- Broad chemical compatibility allows use in most applications Thermally bonded virgin polypropylene construction minimizes extractables

These nominal-rated depth filter cartridges are thermally bonded from 100% virgin polypropylene. Polyflow-G's high dirt-loading, random-fiber polypropylene depth media provides consistent particle retention and protection of upstream filters.

# **Schematic** Selection Process **Applications**

Ultra-Pure Water (UPW)

Introduction

**High-Purity** Solvents Isopropyl Alcohol (IPA)

Hiah-Purity Acids & Bases Hydrofluoric Acid

> High-Purity Acids & Bases Sulfuric Acid

**High-Purity** Acids & Bases Hydrogen Peroxide

Services

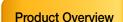
Economical filtration

- High-retention hydrophilic PES membrane
- DI water and dilute acids and bases

Clariflow<sup>®</sup>-WF

- Rating down to 0.04 microns
- 100% integrity tested in cleanroom environment

Clariflow-WE filter cartridges are an economical option for filtering DI water filtration and other dilute aqueous solutions. The filter features a hydrophilic PES membrane and all polypropylene support structure for cost efficient and convenient filtration.



Selection Matrix

#### 13



### Clariflow<sup>®</sup>-F Select

- High-retention hydrophilic PES membrane
- Unique SELECT pleating technology for high flow rate and increased life
- DI water and dilute acids and bases.
- Rating down to 0.02 microns
- 100% integrity tested in cleanroom environment

Clariflow-E-SELECT filter cartridges are optimized for high-flow microelectronics DI water and dilute aqueous-based chemical microelectronics applications. The SELECT pleated, mirrored-anisotropic hydrophilic PES (Polyethersulfone) membrane enables quick and convenient startup without the need for pre-wetting.

#### Worldwide Filtration Manufacturing Locations

#### North America **Compressed Air Treatment**

#### **Gas Separation** & Filtration Division

Airtek/Finite/domnick hunter/Zander Lancaster, NY 716 686 6400 www.parker.com/faf

Balston Haverhill, MA 978 858 0505 www.parker.com/balston

#### **Engine Filtration**

Racor Modesto, CA 209 521 7860 www.parker.com/racor

Holly Springs, MS 662 252 2656 www.parker.com/racor

#### **Hvdraulic Filtration**

**Hydraulic & Fuel Filtration** Metamora, OH 419 644 4311 www.parker.com/hydraulicfilter

Laval, QC Canada 450 629 9594 www.parkerfarr.com

Velcon Colorado Springs, CO 719 531 5855 www.velcon.com

#### **Process Filtration**

domnick hunter Process Filtration

SciLoa Oxnard, CA 805 604 3400 www.parker.com/processfiltration

#### Water Purification

Village Marine, Sea Recovery, Horizon Reverse Osmosis Carson. CA 310 637 3400 www.parker.com/watermakers

#### Europe

#### **Compressed Air Treatment**

domnick hunter Filtration & Separation Gateshead, England +44 (0) 191 402 9000 www.parker.com/dhfns

Parker Gas Separations Etten-Leur, Netherlands +31 76 508 5300 www.parker.com/dhfns

Hiross Zander Essen. Germanv +49 2054 9340 www.parker.com/hzfd

Padova, Italy +39 049 9712 111 www.parker.com/hzfd

#### Engine Filtration & Water Purification

Racor Dewsbury, England +44 (0) 1924 487 000 www.parker.com/rfde

**Racor Research & Development** Stuttgart, Germany +49 (0)711 7071 290-10

#### **Hydraulic Filtration**

Hvdraulic Filter Arnhem, Holland +31 26 3760376 www.parker.com/hfde

Uriala. Finland +358 20 753 2500

#### **Condition Monitoring**

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#### **Process Filtration**

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Selection Process

**Schematic** 

Introduction

Applications

Ultra-Pure Water (UPW)

**High-Purity** Solvents Isopropyl Alcohol (IPA)

High-Purity Acids & Bases Hydrofluoric Acid

High-Purity Acids & Bases Sulfuric Acid

High-Purity Acids & Bases Hvdroaen Peroxide

Services

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**Selection Matrix** 

**Product Overview** 

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